

Istituto Nazionale di Fisica Nucleare

### **HASPIDE COLLABORATION MEETING 09/02/2024**

# **SUMMARY OF PHOTOEMISSION CHARACTERIZATION TESTS IN** PERUGIA

09/02/2024 Peverini Francesca





# **SENSORS UNDER TEST**

Basic detector configurations will be test to assess the performances of the various prototypes.

- a-Si:H on c-Si (Reference);







# **RAMAN SPECTROSCOPY**

Sample films were studied using Raman spectroscopy, it allows to measure the concentration of hydrogen in the sample.

The amount of hydrogen has influence on the creation of defects and stability of a-Si:H films

All Raman spectra were measured with the use of Raman spectrometer in the backscattering geometry at room temperature using the 532 nm line of an Ar+ laser as a source.

The power of the laser beam reaching the sample was **3-30mW**.

The spectral range of the spectrometer is from 250 to 3500 cm -1. The frequency shifts were calibrated using the crystalline silicon emission line (520 cm-1)







# **RAMAN SPECTROSCOPY**





Example of the deconvolution of the Raman spectrum into Gaussian peaks, broad peaks can be recognised:

- **Transverse acoustic**
- Transverse optical
- Longitudinal acoustic

**Longitudinal optical** 

Vibration of the Si–Si bonds

The peak at about **480 cm<sup>-1</sup>**, is indicative of the short-range disorder; an increase in the half-width and a shift in the position toward lower frequencies indicate an increase in short-range disorder.





# **RAMAN SPECTROSCOPY**



You can also see peaks due to scattering on the stretching vibrations of the Si–H, Si–H<sub>2</sub> and Si–H<sub>3</sub> bonds.

Ratio of the Si-H<sub>n</sub> to Si-Si scattering intensities:



According to literature, the ratios of Raman scattering cross-sections for SiH to SiSi bonds is equal to  $0.40 \pm$ 0.04.





# **RAMAN SPECTROSCOPY**

Characteristic parameters derived from these spectra

Sample Substrate	ΤΟ	2LA	<b>2TO</b>	Si-H	Si-H <sub>2</sub>	<u>Si-H<sub>3</sub></u> <u>?</u>
Kapton	460	570	910	1990	2094	2174
c-Si	472	/	928	2012	2170	/
Glass	480	602	930	2028	2153	2200

Can be used to quantify the short-range order in a-Si:H films. Surface roughness effect?



detectors deposited on Kapton are more amorphous (more defects) and with less hydrogen content

That might be why Kapton devices have lower sensitivity





# **RAMAN SPECTROSCOPY**

The laser can transform sample from amorphous to **crystalline silicon** by melting the silicon for several nanoseconds.

The distribution of possible states for amorphous silicon leads to abroad Raman band centered at 480 cm<sup>-1</sup>, while crystalline silicon exhibits a **sharp peak at 520 cm<sup>-1</sup>** 

Laser power increase, as well as the position of the peak shifts to the higher wavenumber values, suggesting that the crystallinity of the treated film increases and the crystalline grains are getting larger.

Intensitry (a.u.)





# **RAMAN SPECTROSCOPY**



Amorphous silicon deposited on c-Si (assembled to form a detector) has greater laser resistance, comparable to that of the device deposited on kapton, both can achieve higher laser intensities (30 mW) than aSiH/cSi film.







# **IPES SPECTROSCOPY**



### **IPES Inverse Photoemission**

A beam of electrons of defined energy and momentum impinge on the surface sample, coupling with **unoccupied** electronic states above the vacuum level, and radiatively decaying into their lower-empty states. Emitted photons are collected through a Geiger-Müller detector.

It is a complementary technique to photoemission spectroscopy; together they allow us to estimate the gap and quantify the **defects**.











# **IPES SPECTROSCOPY**



